

# GaAs Panel Session – EuMIC 2011

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Connecting the Digital World to the Global Network®

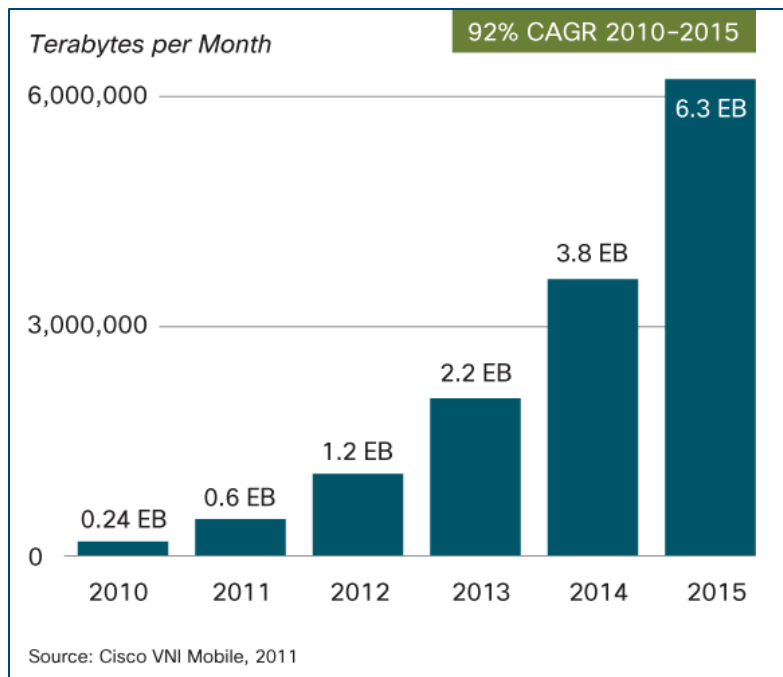
**TriQuint**   
SEMICONDUCTOR

# Agenda

- ◆ RF Markets
- ◆ Advantages of Compound Semiconductors
- ◆ RF Process Technologies

# RF Applications Markets Exploding

## ◆ Mobile Devices Data Traffic



## ◆ Higher Power, Higher Efficiency

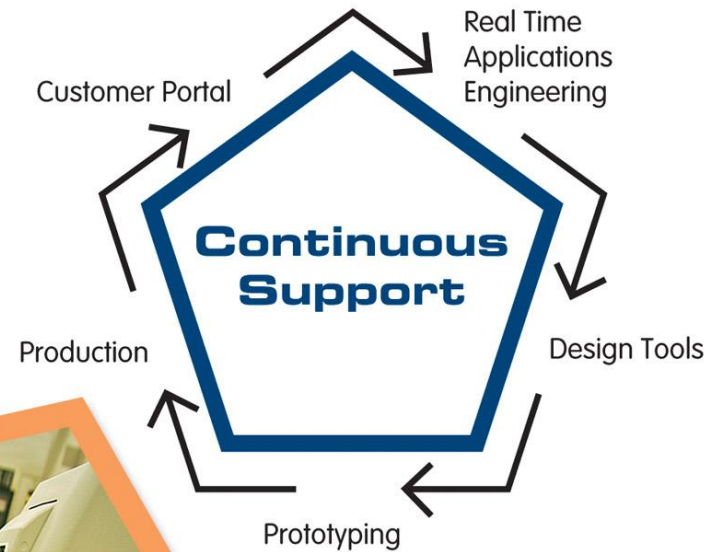


# Advantages of Compound Semiconductor for RF

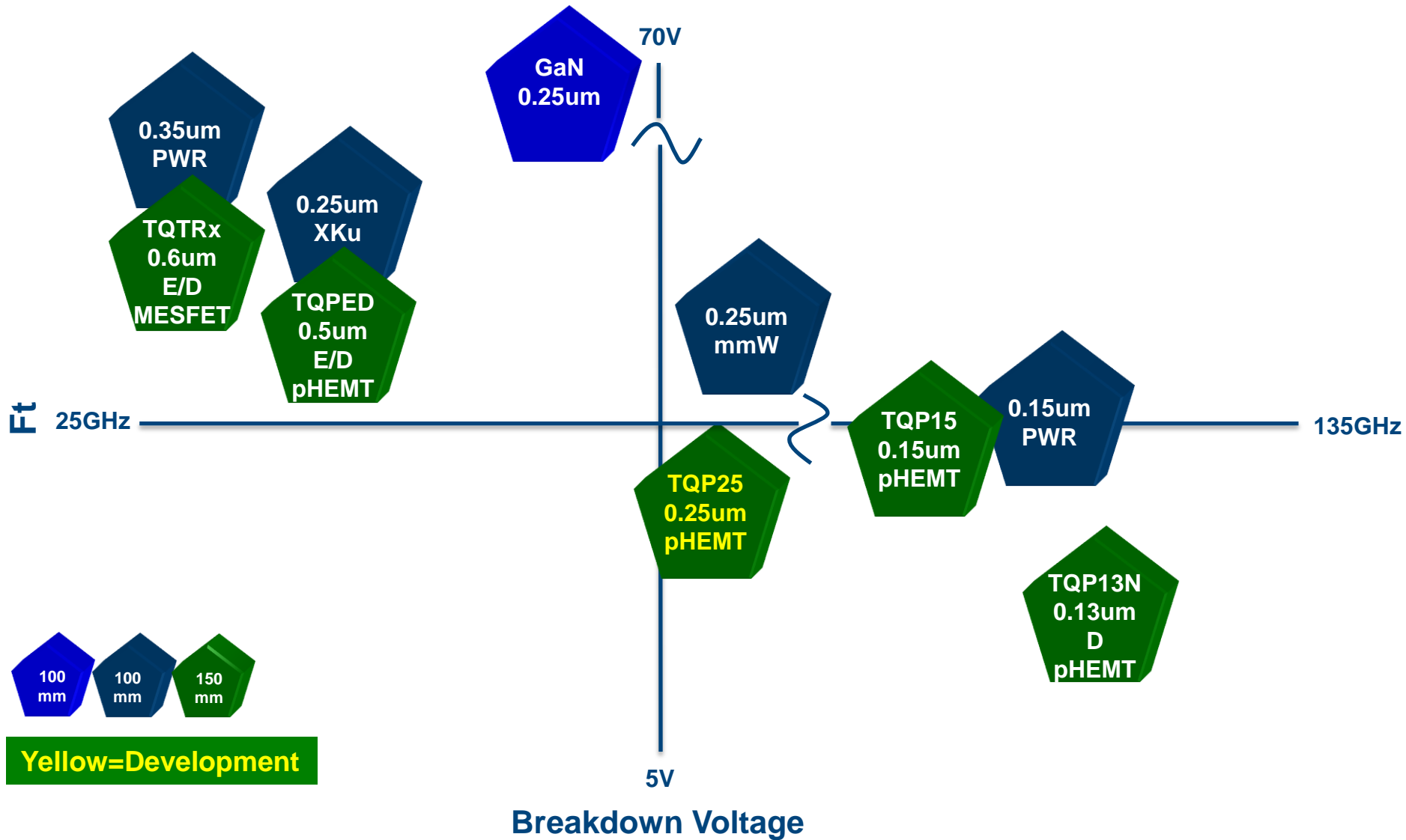
- ◆ Superior material properties vs silicon technologies
  - GaAs: larger band gap, higher mobility, hetero structures
  - GaN: very large band gap, high voltage, high  $T_j$  operation
- ◆ GaAs
  - Superior noise figure, low insertion loss linear RF switch and PA performance
  - Semi-insulating substrate (better isolation, higher Q passives)
  - High-voltage PA solutions
  - Lower development cost
- ◆ GaN
  - Superior high-voltage, high-frequency, high-temperature performance
- ◆ Competition
  - SiGe
  - Low / high voltage LDMOS
  - SOI-CMOS, bulk CMOS

# TriQuint Foundry

- ◆ Leading compound semiconductor foundry supplier for more than 25 years
- ◆ Broadest range of GaAs and GaN foundry technologies
- ◆ Unmatched support and service



# Foundry FET Processes



# Commercializing mmWave Markets – Optical Gates

**TQPED**  
0.5 $\mu$ m E/D

Ft = 27 GHz

Integrated WLAN,  
Switches

**TQP25**  
0.25 $\mu$ m D  
0.35 $\mu$ m E

Ft = 55 GHz

Handset Switches,  
LNAs, PtP,  
Ku-band PAs

**TQP15**  
0.15 $\mu$ m D

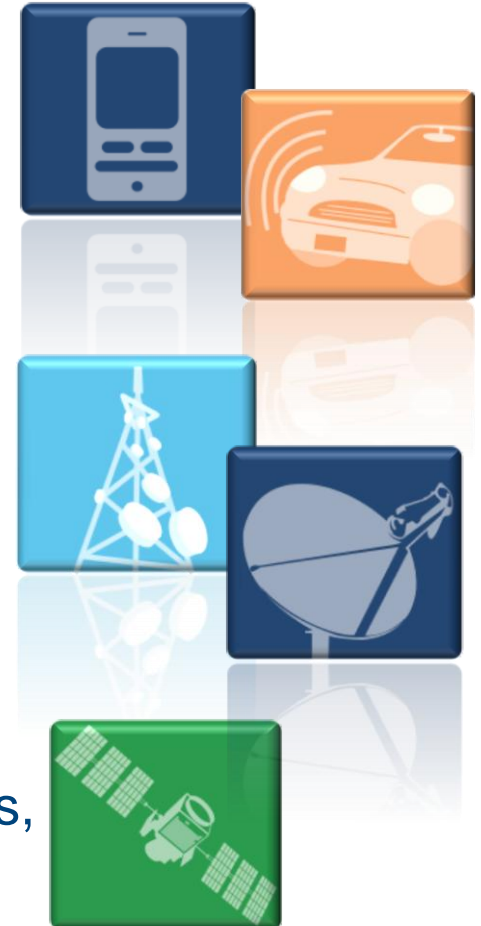
Ft = 80 GHz

VSAT, PtP,  
Ka-band PAs

**TQP13**  
0.13 $\mu$ m D

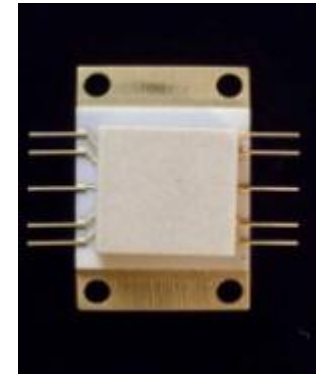
Ft = 100 GHz

Low Noise Amplifiers,  
Auto Radar, WPAN,  
Satellite, Imaging

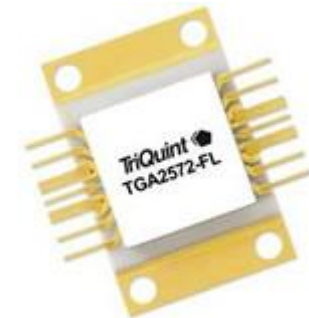


# Advantages of Gallium Nitride on SiC

- ◆ GaN provides 2x to 4x Power Density for RF amplifiers
  - Combination of high current and high voltage operation
  - Higher W/mm enables less combining loss, hence increased PAE
  - Higher Vd operation enables system power efficiency improvement
- ◆ Very high thermal conductivity SiC substrate
  - ~10x that of GaAs, benefit for higher power/CW operation
- ◆ Reliable at high junction temperatures
  - MTTF of 1E6 Hours at 200°C
- ◆ Capable of high frequency operation
  - GaN applications span UHF to W-band to THz
- ◆ Excellent noise figure
  - $NF_{min}$  equivalent to comparable GaAs pHEMT
  - Higher input survivability



TGA2514; 6.5W Ku-band GaAs HPA



TGA2572; 20W Ku-band GaN HPA





















# GaN R&D Programs

- ◆ DARPA WBS (Wide Bandgap Semiconductor) - \$32.3M
  - Develop GaN highest power wideband amplifiers
  - Advance GaN materials, processing and MMIC design technologies
  - Deliver PA modules to DoD
  
- ◆ DARPA NeXt (Advanced Nitride Electronics) - \$16.2M
  - Develop 500GHz Nitride based transistors using sub 0.1 $\mu$ m GaN process
  - Monolithically integrated E&D mode transistors
  
- ◆ Defense Production Act Title III - \$17.5M
  - GaN manufacturing development contract
  - Increase yield, lower costs and improve time-to-market cycles for defense and commercial GaN integrated circuits.

# Design – Tools and Applications Support

- ◆ Industry standard for pHEMT models
- ◆ Senior applications staff
  - Design Reviews, circuit consulting, apps support

## EDA Tools Provider

	 Agilent Technologies	 AWR	 cadence™	 Mentor Graphics	 ICED
SCHEMATIC CAPTURE					
SIMULATION					
LAYOUT					
LAYOUT VERIFICATION					

# Summary

- ◆ GaAs and GaN best technologies for RF applications
- ◆ Broad technology portfolio required to address various RF markets
- ◆ Optimized design tools and experienced applications support required to meet demanding RF specifications

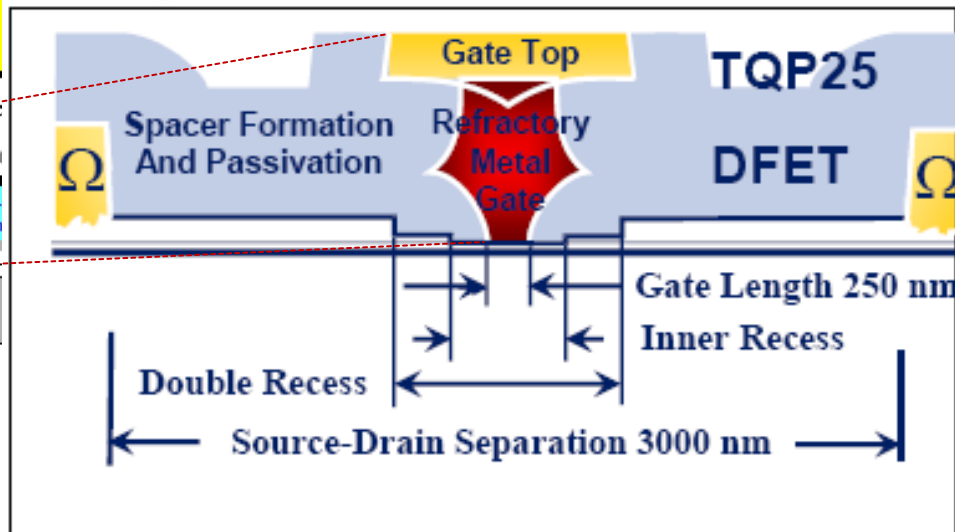
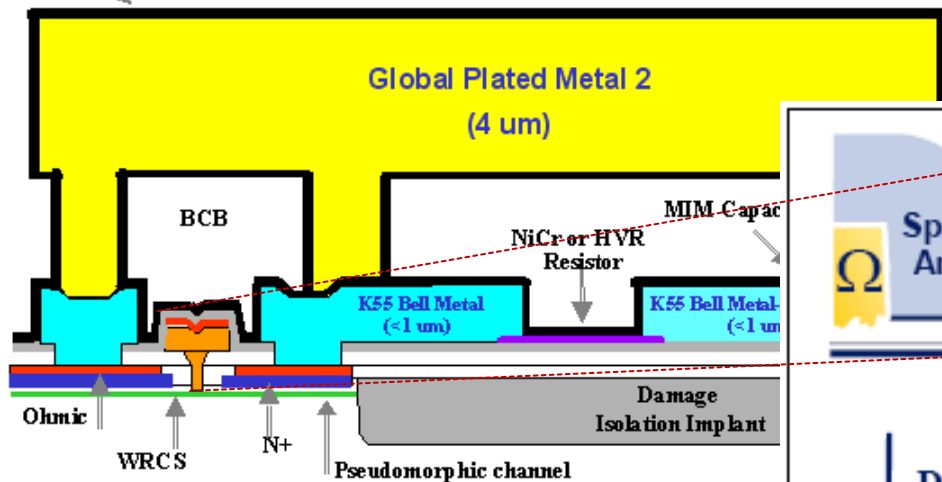
# Backup Slides

# Process Portfolio Overview

Technology	Attributes	TriQuint Process Name	Wafer Size
<b>pHEMT</b>	0.5µm E/D Mode FETs – Mixers, LNAs, Switches	TQPED	150mm
	0.25µm E/D Mode FETs – Switches & Amplifiers	TQP25	150mm
	0.15µm D-Mode – mmW Amplifiers	TQP15	150mm
	0.13µm Low Noise	TQP13-N	150mm
	Highest Power pHEMT Density	0.35µm PWR pHEMT 3MI	100mm
	High Power Through 50 GHz	0.25µm mmW pHEMT 3MI	100mm
	High Power Through 20 GHz	0.25µm XKu pHEMT 3MI	100mm
	Higher Power Density Through 80 GHz	0.15µm PWR pHEMT 3MI	100mm
<b>MESFET</b>	E/D Mode FETs – Mixers, LNAs, Switches	TQTRx	150mm
	D-Mode FETs – Higher Power	TQHiP / HA2	150mm
<b>Heterostructure FET</b>	High Linearity	0.5µm HFET 2MI	100mm
<b>InGaP HBT</b>	InGaP HBT 3 Metal Interconnect	TQHBT3	150mm
<b>BiHEMT</b>	Integrated E/D pHEMT & HBT	TQBiHEMT	150mm
<b>GaN</b>	Highest Power Density	0.25µm GaN 3MI	100mm
<b>Vertical PIN Diode</b>	Low Loss Switches	VPIN 2MI	100mm
<b>Passives</b>	Integrated Passives	TQRLC	150mm
<b>Flip Chip</b>	Copper Bump	CuFlip™	150mm

# Reducing the Cost of mmWave with Optical Gates

Passivation Nitride



- Gate length drives Ft
- Ft drives frequency capability

	E-Beam	DUV Optical	Spacer-Based Optical
Cost	●	●	●
Throughput	●	●	●
Performance	●	●	●

# HBT Process Overview

